

5. (Twice Amended) The integrated metal etch tool of claim 15 wherein said strip chamber means conducts chemical down stream etching at temperatures greater than 200°C ^{thereby forming} to form a passivation layer on the Al/Cu metal line surface.

REMARKS

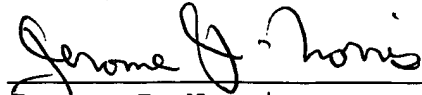
A summarization of the improved integrated metal etch tool for removing post-RIE polymer rails from Al/Cu metal lines of a semiconductor structure of the invention is provided to facilitate easier grasp of the integrated metal etch tool containing therein strip, vacuum and deionized rinse chamber means compared to the different structures disclosed in the Chen and Davis et al. references.

In the art of making semiconductor structures in which there must be removal of post-RIE polymer rails that are formed on a Al/Cu metal line, applicants have invented interfaceable strip, vacuum and rinse chamber means within an integrated metal etch tool that permits removing the sidewall polymers left behind after the metal (Al/Cu) RIE process. The novel chamber means of the interfaced metal etch tool performs the chemistry (either post resist strip or prior to resist strip), thereby allowing a final rinse step of only using deionized water as a rinse.

It is respectfully requested that the foregoing clearer

description of the invention be taken into consideration in
advance of the examination of this application on the merits.

Respectfully submitted,

A handwritten signature in cursive script, reading "Jerome J. Norris", is written over a horizontal line.

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